Novel Techniques for Additive Manufacturing of Functional Materials

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Motivation: Agile Production of 3D Microsystems



Key capability \rightarrow Printing high-quality functional materials (electrical, optical, magnetic)



- Industry direction for 3D printers focused on tool development
 - Large-format single-material industrial printers for manufacturing
 - Fast, inexpensive, low resolution single-material hobby printers
 - Limited to a small set of materials for single material printing
- Currently available materials for 3D printing technologies limited in materials and functionality
 - Design new 3-D-print-compatible low-loss dielectrics and conductors
 - Develop gradient and concurrent multimaterial printing processes
 - Develop new techniques for direct writing microelectronics quality structures



Envisiontek Ultra DPL

Makerbot Replicator2



Expand beyond materials that can be printed to materials that need to be printed



3D Printing Technologies



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3D Printing Technologies



Can print metals, ceramics, polymers, and combinations of multiple materials within one structure

Direct-write 3D printing provides the most versatile platform for fabricating multimaterial microsystems



- Introduction and Motivation Agile production of 3D Microsystems
- Direct ink writing of novel classes of materials for RF devices:
 - Triblock copolymers
 - Metal oxide composites
 - Multicomponent materials
 - Conductive materials
- Microplasma sputtering An alternative for direct writing of conductive thin films
- Summary



- Material dissolved in a volatile solvent is extruded
- Solvent rapidly evaporates leaving rigid structures
- Printing nozzle location is robotically controlled



• Available 3D materials for RF applications are limited

- We are exploring direct writing of novel classes of materials:
 - Triblock Copolymer Dielectric Materials
 - Metal Oxide Composite Dielectric Materials
 - Multicomponent Materials
 - Conductive Materials

Solvent Casting of Dielectric Material



This structure was printed out of a nozzle with a 233 µm diameter on Aerotech printer



- Styrenic triblock copolymers are commercial polymers with each block contributing to the polymer properties
 - Styrene and polyethylene are low RF loss dielectrics
 - Triblock composed of polystyrene and an aliphatic polymer (polyisoprene, polybutadiene, ethylene-butylene copolymer) should also have low loss
- Triblock copolymers are good candidates for 3D printing
 - Styrene end-blocks clump together for crosslinking reduced feature distortion
 - High viscosity at low shear rate no shear thinning
 - Extrusion induces polymer alignment







3D Printed RF Components with Triblock Copolymers

- Inks formulated with styrene/divinyl benzene casting solvent to reduce shrinkage
- UV curing added to crosslink solvent during printing

Modified 3D printer for UV curing during deposition











Low-loss Dielectric Materials for Millimeter-Wave RF Applications

- Device operation in 26-40 GHz range requires extremely low-loss dielectric materials
 - Materials used at lower frequency have losses that are not tolerable at mmW
 - Loss increases as frequency increases
- 3D printable materials with relative permittivities > 10 are not available at mmW
 - This capability would allow for new options in device design and capabilities



Add ceramic nanoparticles to raise the relative permittivity of inks



- Ceramic nanoparticles are combined with triblock copolymers to create 3D printable inks
- Low loss dielectrics with relative permittivity ranges from 2.2-24.6 have been generated
- System can be predictively tailored using effective medium theory



Material (vol. %)	Relative Permittivity (ε')	Loss Tangent (ɛ"/ɛ')	
SIS Bolymor	(34 GHZ)	(34 GHZ)	
	2.2	0.002	
$TiO_{3}/SIS(30:70)$	5.9	0.003	
SrTiO₃/SIS (30 : 70)	10.1	0.032	
Al ₂ O ₃ /SIS (60 : 40)	5.2	0.008	
TiO ₂ /SIS (60 : 40)	13.8	0.028	
SrTiO ₃ /SIS (30 : 70)	24.6	0.050	
d 23 vol.% ₃/SIS ink	Printed 45 vol.% TiO ₂ /SIS ink	Printed 30 vol.% SrTiO ₃ /SIS ink	
	Material (vol. %) SIS Polymer $AI_2O_3/SIS (30 : 70)$ $TiO_2/SIS (30 : 70)$ $SrTiO_3/SIS (30 : 70)$ $AI_2O_3/SIS (60 : 40)$ $TiO_2/SIS (60 : 40)$ $SrTiO_3/SIS (30 : 70)$ d 23 vol.% SIS ink	Material (vol. %) Relative Permittivity (ϵ ') (34 GHz) SIS Polymer 2.2 Al ₂ O ₃ /SIS (30 : 70) 3.4 TiO ₂ /SIS (30 : 70) 5.9 SrTiO ₃ /SIS (30 : 70) 10.1 Al ₂ O ₃ /SIS (60 : 40) 5.2 TiO ₂ /SIS (60 : 40) 5.2 TiO ₂ /SIS (60 : 40) 13.8 SrTiO ₃ /SIS (30 : 70) 24.6 Colored 23 vol.% Printed 45 vol.% SIS ink Printed 45 vol.% Violation TiO ₂ /SIS ink	

1000 um

Relative permittivity and loss tangent can be controlled by nanoparticle volume fraction

Linewidth 233 µm



Printed Filters with Metal Oxide Composite Inks

- Band-pass filters
 - Printed with 200 µm nozzle
 - Transmission measured in 26.5-40 GHz (K_a band)
- Block copolymer device
 - Device conforms well to the model, slightly outperforming it
- Composite ink device
 - 23 vol. % Al₂O₃ particles was tested
 - Device was printed to the same dimensions
 - Device conforms well to model, slightly outperforming it

Higher dielectric material resonance peaks shifted to lower frequencies as expected

Lis M.; Plaut M.; Zai A.; Cipolle D.; Russo J.; Fedynyshyn T. ACS Appl. Mater. Interfaces 2016 8 (49), 34019.







- Combining multiple inks with different dielectric properties enables:
 - Distinct material structures
 - Continuously variable dielectric materials for novel electromagnetic properties

- Unique devices enabled
 - Miniaturized antennas for wideband communication
 - Graded dielectric allows smaller flat (2D v. 3D) antennas with broader range and higher gain



Calculated Archimedean Spiral Antenna

Multimaterial printing allows for complex designs conventional approaches cannot achieve







- Active mixing enables combination of highly viscous materials
 - Ink flow is volumetrically controlled by the printer
 - Inks are mixed within the chamber prior to deposition



Active Mixing Nozzle





Demonstration spiral structure is backlit to show transparency of inner polymer rings

Polymer – Clear (ϵ = 2.2) TiO₂ composite ink – Opaque (ϵ = 13.8)

Gradient dielectric printing opens up new frontiers in RF device and antenna design



3D printed conductive inks need high temperature (250 - 500°C) sintering to achieve conductivity But - many 3D printed dielectric materials decompose or deform during high temperature sintering

Material	Resistivity (Ω·m)	Conductivity (S/m)	Conductivity Relative to Bulk Silver (%)
Bulk Silver	1.6 * 10 ⁻⁸	6.3 * 10 ⁷	100
Low Temperature Commercial Silver Ink	7.4 * 10 ⁻⁶	1.4 * 10 ⁵	0.2
LL G2 Silver Ink	1.8 * 10 ⁻⁷	5.7 * 10 ⁶	9.1
LL G2 Gold Ink	8.3 * 10 ⁻⁷	1.2 * 106	1.9*

*2.9 % of bulk gold

LL G2 Silver Ink

We have developed conductive inks with favorable properties:

- Compatible with our triblock copolymer system
- Conductive filler can be tailored in a modular fashion
- G2 Silver can be printed at 100 µm resolution and RMS roughness of ~600 nm
- Processed at RT or 70°C

We can print conductive traces with 9% conductivity relative to bulk silver without annealing



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Direct Write of Microelectronics Quality Conductors: Atmospheric Microplasma Sputtering

Concept: Small-scale plasma chamber for atmospheric direct deposit of thin films



Why Microplasmas?

- Reduction in scale enables stable operation at atmospheric pressures
- Material agnostic
- Substrate agnostic
- No post-processing required





Atmospheric Microplasma Sputtering System



Compact for Integration with 3D Printer Continuous wire-feed mechanism



Modular Assembly



<image>

Printing Gold Line on Paper





Atmospheric microplasma system used to demonstrate:

- Deposition of gold lines with linewidth < 100 μm (focused), 1 μm (shadow mask aperture)
- Resistivity > 1.4 x 10⁻⁷ Ω•m (5x gold interconnect)
- Deposition on planar conducting and insulating substrates





• Sputter deposited films exhibit varying morphologies, columnar structure



- Model developed to predict film quality based on:
 - Target-to-substrate gap
 - Focus bias voltage
 - Backplane bias
 - Inner and outer gas flows
- Model predicts increased film continuity with:
 - Higher backplane negative bias
 - Smaller target-substrate gap, unbiased backplane
 - Higher outer flow rate, unbiased backplane

Film morphology and properties can be tailored with deposition conditions



Kornbluth, Y. et al, Nanotechnology 2019 30 (28), 285602.



Printing Multiple Materials



Print head mounted on Meca500 robot arm for precision writing

2-target capability



sheath

electrodes



Summary - Functional Materials Printing Technologies



We have developed a suite of functional materials and processes enabling agile production of 3D microsystems beyond those achievable with conventional methods



Thank you for your attention.

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